

Laser Direct-Write Processing

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Guest Editors

Abstract

Direct-write techniques enable computer-controlled two- and three-dimensional pattern formation in a serial fashion. Among these techniques, the versatility offered by laser-based direct-write methods is unique, given their ability to add, remove, and modify different types of materials without physical contact between a tool or nozzle and the material of interest. Laser pulses used to generate the patterns can be manipulated to control the composition, structure, and even properties of individual three-dimensional volumes of materials across length scales spanning six orders of magnitude, from nanometers to millimeters. Such resolution, combined with the ability to process complex or delicate material systems, enables laser direct-write tools to fabricate structures that are not possible to generate using other serial or parallel fabrication techniques. The goal of the articles in this issue of *MRS Bulletin* is to illustrate the range of materials processing capabilities, fundamental research opportunities, and commercially viable applications that can be achieved using recently developed laser direct-write techniques. We hope that the articles provide the reader with a fresh perspective on the challenges and opportunities that these powerful techniques offer for the fabrication of novel devices and structures.

Introduction

From the earliest work on laser interactions with materials, direct-write processes have been important and relevant techniques to modify, add, and subtract materials for a wide variety of systems and for applications such as metal cutting and welding. In general, direct-write processing refers to any technique that is able to create a pattern on a surface or volume in a serial or "spot-by-spot" fashion. This is in contrast to lithography, stamping, directed self-assembly, or other patterning approaches that require masks or preexisting patterns. At first glance, one may think that direct-write processes are slower or less important than these parallelized approaches. However, direct-write allows for precise control of material properties with high resolution and enables structures that are either impossible or impractical to make with traditional parallel techniques. Furthermore, with continuing developments in laser technology providing a decrease in cost and an increase in repetition rates, there is a plethora of applications for which laser direct-write (LDW) methods are a fast and competitive

way to produce novel structures and devices. This issue of *MRS Bulletin* seeks to assess the current status and future opportunities of LDW processes in the context of emerging applications.

There are many types of direct-write techniques used in science and engineering.¹ For instance, previous *MRS Bulletin* issues discussed topics such as inkjet printing (November 2003) and focused ion-beam processing (February 2000, July 2001, and December 2005). In the most classical sense, engraving or milling can be considered a direct-write process, since a tool or stylus makes contact with a surface and is moved in a desired pattern to produce a feature. The coupling of a high-powered laser with direct-write processing enables similar features to be produced without requiring physical contact between a tool and the material of interest. Because of this, few techniques share the versatility of LDW in adding, subtracting, and modifying different types of materials over many different length scales, from the nanometer to the millimeter scale.

In LDW, the beam is typically focused or collimated to a small spot (in industrial processes, this "small" spot can be several millimeters in diameter). Patterning is achieved by either rastering the beam above a fixed surface or by moving the substrate or part within a fixed beam. An important feature of LDW is that the desired patterns can be constructed in both two and three dimensions on arbitrarily shaped surfaces, limited only by the degrees of freedom and resolution of the motion-control apparatus. In this manner, LDW can be considered a "rapid prototyping"²⁻⁴ tool, because designs and patterns can be changed and immediately applied without the need to fabricate new masks or molds.

The key elements of any LDW system can be divided into three subsystems: (1) laser source, (2) beam delivery system, and (3) substrate/target mounting system (see Figure 1). At the heart of any LDW process is the laser source. Typical experiments and applications use anywhere from ultrafast femtosecond-pulsed systems to continuous-wave systems employing solid-state, gas, fiber, semiconductor, or other lasing media. In choosing an appropriate source, one must consider the fundamental interactions of lasers with the material of interest. This requires knowledge of the pulse duration, wavelength, divergence, and other spatial and temporal characteristics that determine the energy absorption and the material response. In beam delivery, there are a variety of ways to generate a laser spot, including fixed focusing objectives and mirrors, galvanometric scanners, optical fibers, or even fluidic methods such as liquid-core waveguides⁵ or water jets.⁶ The choice depends on the application demands, for instance, the required working distances, the focus spot size, or the energy required. The ultimate beam properties will be determined by the combination of laser and beam delivery optics. Finally, the substrate mounting is done in accordance with experimental or industrial requirements and can be manipulated in multiple directions to achieve a desired result. Robotics and active feedback control, on either the substrate or beam delivery optics, can add further design flexibility to the technique.

There is a vast range of LDW processes. For the purposes of this issue, we categorize them into three main classes: laser direct-write subtraction (LDW⁻), where material is removed by ablation; laser direct-write modification (LDWM), where material is modified to produce a desired effect; and laser direct-write addition (LDW⁺), where material is added by the laser.

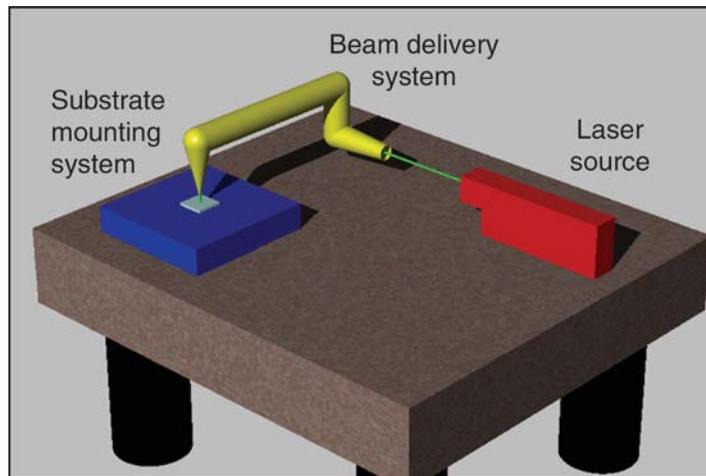


Figure 1. Schematic illustration of a laser direct-write system. The basic components of an LDW system are (left to right) a substrate mounting system, a beam delivery system, and a laser source. Motion control of either the beam delivery system or the substrate mounting system is typically accomplished using computer-assisted design and manufacturing (CAD/CAM) integrated with the laser source.

Laser Direct-Write Subtraction (LDW-)

LDW- is the most common type of laser direct-write. In general, this entails processes that result in photochemical, photothermal, or photophysical ablation on a substrate or target surface, directly leading to the features of interest.⁷ Common processes include laser scribing, cutting, drilling, or etching to produce relief structures or holes in materials in ambient or controlled atmospheres.⁸ Industrial applications using this technique range from high-throughput steel fabrication, to inkjet and fuel-injection nozzle fabrication,^{9,10} to high-resolution manufacturing and texturing of stents or other implantable biomaterials.¹¹ At a smaller scale, inexpensive benchtop laser cutting and engraving systems can be purchased by the hobbyist or small company for artistic and architectural renderings. More recent developments in LDW- include chemically assisted techniques such as laser-drilling ceramics or biomaterials and laser-induced backside wet etching (LIBWE) of glass.^{12,13} In fact, one may also consider laser cleaning to be a controlled LDW- process.¹⁴

The fundamental interactions leading to material removal can be thermal or athermal, depending primarily on the material/environment characteristics and the pulse duration of the laser. These interactions have a direct effect on the quality of the resulting features. For instance, a heat-affected zone (HAZ) tends to occur in the vicinity of thermally removed material. This region has structures and properties that can differ from the bulk material and

can exhibit additional surface relief. Either of these effects may be beneficial or detrimental, depending on the application. In contrast, athermal and multiphoton absorption processes caused by ultrafast lasers can reduce the formation of a HAZ and enable features smaller than the diffraction limit.^{15,16}

Laser Direct-Write Modification (LDWM)

In LDWM, the incident laser energy is usually not sufficient to cause ablative effects but is sufficient to cause a permanent change in the material properties. Typically, these processes rely on thermal modifications that cause a structural or chemical change in the material. A common example of such processes is the rewritable compact disc, in which a diode laser induces a phase transition between crystalline and amorphous material.¹⁷ In industrial applications, one may consider laser cladding, where a surface layer different from the bulk material is produced through melting and resolidification,¹⁸ or solid free-form fabrication (SFF) approaches such as selective laser sintering (SLS),¹⁹ as important modifying processes that would fall under the umbrella of LDWM.

Many LDWM applications require a specific optical response in the material of interest beyond simple thermal effects. Optically induced defects or changes in mechanical properties can lead to many non-ablative material modifications. For instance, photoresists respond to light by breaking or reforming bonds, leading to

pattern formation in the material. Alternatively, LDW can cause defects in photo-etchable glass ceramics²⁰ or other optical materials through single- and multiphoton mechanisms,²¹ enabling novel applications in optical storage,²² photonic devices,^{23,24} and microfluidics.²⁵

Laser Direct-Write Addition (LDW+)

LDW+ is perhaps the most recent of the laser direct-write processes. In this technique, material is added to a substrate using various laser-induced processes. Many techniques are derived from laser-induced forward transfer (LIFT), where a sacrificial substrate of solid metal is positioned in close proximity to a second substrate to receive the removed material.²⁶ The incident laser is absorbed by the material of interest, causing local evaporation. This vapor is propelled toward the waiting substrate, where it recondenses as an individual three-dimensional pixel, or voxel, of solid material. Such an approach has found important use in circuit and mask repair and other small-scale applications where one needs to deposit material locally to add value to an existing structure. This general technique has significant advantages over other additive direct-write processes, in that these laser approaches do not require contact between the depositing material and a nozzle, and can enable a broad range of materials to be transferred. Variations on the general LIFT principle allow liquids, inks, and multiphase solutions to be patterned with computer-controlled accuracy for use in a variety of applications such as passive electronics or sensors.^{27,28}

Alternatively, LDW+ techniques can rely on optical forces to push particles or clusters into precise positions,²⁹ or on chemical changes in liquids and gases to produce patterns. For instance, laser-induced chemical vapor deposition,³⁰ or multiphoton polymerization schemes of liquid photoresists,³¹ can be used to fabricate three-dimensional stereographic patterns. Examples of this have been demonstrated and show promise for many applications such as fabricating photonic structures or biological scaffolding.

Highlights of Articles in This Issue

The breadth of LDW processing makes it impossible to cover the entire topic in a single *MRS Bulletin* issue. The situation is further complicated by the fact that many LDW processes have either grown into mature fields in and of themselves (laser cutting, welding, etc.) or provide ample topical material for an independent *MRS Bulletin* issue (solid free-form fabrication,

laser cleaning, fiber laser development, etc.). Therefore, we restrict ourselves to LDW processes developed in the past few years that provide opportunities for growth beyond the traditional industrial applications. Clearly, this coverage is not exhaustive, and there are many other LDW approaches that could be discussed. However, the reader of this issue should get a good sense of the possibilities of LDW.

We have purposely avoided focusing on femtosecond laser techniques because the August 2006 issue of *MRS Bulletin* on "Ultrafast Lasers in Materials Science" covered this topic in detail, including some LDW approaches. Femtosecond lasers are very important in many of the newer LDW approaches, as they enable higher-resolution features, detailed control over structures, and unique nonthermal processing capabilities. The reader is referred to the earlier *MRS Bulletin* for more information.

In the first article in this issue, by Grigoropoulos et al., we look at approaches for LDW – that can produce features significantly smaller than the diffraction limit of light. In this approach, a near-field phenomenon is utilized that radiates the electromagnetic field to the region directly below an atomic force microscope (AFM) tip, removing material in an area as small as 10 nm. Rastering is controlled by the motion of the AFM stage, and various features can be produced. By coating the tip with metal, deposition on the nanoscale by LDW+ can also be accomplished.

Two articles on LDW+ follow. In the first, by Arnold et al., we look at LDW+ of complex materials, including biological materials such as cells and proteins, electrochemical materials for energy storage, and even complete semiconductor devices. The approach relies on laser forward transfer of multicomponent suspensions composed of different liquid and/or solid materials, which allows for deposition without harming sensitive material properties. This technique can be further combined with LDWM or LDW – to perform postdeposition processing with the same tool. Next, Stuke et al. turn our attention to the LDW+ fabrication of three-dimensional structures such as cages for trapping particles and photonic structures for guiding light. In this technique, a laser-based chemical vapor deposition method produces highly conductive, freestanding metal features. One particularly interesting application is the production of carbon nanotubes and wires in an LDW fashion.

One of the key advantages of LDWM for material modification, in contrast to many parallel approaches, is the ability to apply a unique photon flux at each laser spot. Livingston and Helvajian discuss a real-time sequencing approach that programs the incident laser pulses to enable distinctive, site-selective processes. This can be applied to photomodifiable glasses and glass ceramics to produce complex features that would be difficult or impossible to make by other methods.

Finally, we look toward the future of LDW with Sugioka et al., who discuss the global industrial aspects of LDW processing. Cutting-edge applications in Europe, the United States, and Japan are discussed, with implications for long-term growth.

Summary

One of the unique attributes of laser direct-write processes is that the general methodology enables a complete range of materials processing in order to fabricate devices and structures. These techniques make it possible for a single tool, located in the research lab or on the factory floor, to design and build an entire part with precise control over the composition, structure, and properties on each laser pulse.

Although that vision of LDW has not been reached, the articles in this issue of *MRS Bulletin* cover additive, subtractive, and modification methods and demonstrate a commercially viable technology with abundant opportunities for fundamental research that will continue to push advancements in the field. Ideally, these approaches lend themselves to rapid prototyping and small-scale production where unique features are needed for a desired application. However, they also find important implementation in commercial ventures where high-repetition-rate, multi-beam laser systems allow LDW to compete with parallel processing in speed and cost. The impact of LDW processes in advanced applications will continue to grow as new methods and technologies become available and the demands for more precise control over material structures and properties are met.

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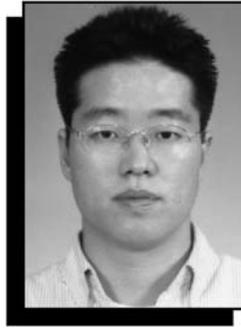
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composed of glass ceramic materials.

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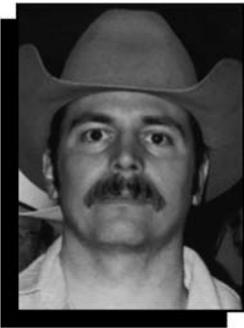
Koji Sugioka

chemistry, he became a staff member at MPI Göttingen, where he heads the Laser Chemical Processing of Materials group. He has worked at the University of Southern California, ENEA Frascati in Italy, RIKEN in Japan, and Hewlett-Packard Laboratories in Palo Alto, California. Stuke received the Otto Hahn Medal from the Max Planck Society and is editor in chief of *Applied Physics A, Materials: Science and Processing*.

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Sugioka has received several awards for his



R. Stanley Williams

research and inventions in the area of laser microprocessing. He has published more than 100 articles, given more than 40 invited talks at international conferences and more than 50 invited talks at domestic conferences, and holds over 20 patents or pending patents. He has served as a conference chair, co-chair, and committee member for numerous international

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